

ABSTRACT**Workpiece holder, system, and operating method for PECVD**

The present invention relates to a workpiece holder (1) for a plasma-enhanced chemical vapour deposition system (50), to a system (50) of this kind, and to an operating method (100) for a system (50) of this kind. The workpiece holder (1) is designed to produce a plasma from a process gas surrounding the workpiece holder (1). According to the invention, the workpiece holder (1) is also designed to heat the surroundings of the workpiece holder (1) to a process temperature envisaged for the vapour deposition.

Fig. 1